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Docket No. 50261-2

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

APPLICANT: G. Taylor et al.  
SERIAL NO.: 09/330,418 EXAMINER: S. Lee  
FILED: June 11, 1999 ROUP: 1752  
FOR: NOVEL POLYMERS AND PHOTORESIST COMPOSITIONS

THE HONORABLE COMMISSIONER OF PATENTS AND TRADEMARKS  
WASHINGTON, DC 20231

SIR:

AMENDMENT

Please amend the above-identified application as follows.

IN THE CLAIMS

Please cancel claims 19-28 without prejudice.

Please add the following new claims.

29. A positive-acting photoresist composition comprising a photoacid generator and a polymer,

the polymer 1) being substantially free of aromatic groups; and 2) comprising polymerized acrylate groups and pendant acid-labile groups that contain an optionally substituted cycloalkyl group having 3 or 4 ring carbon atoms.

30. The photoresist of claim 29 wherein the polymer comprises pendant acid-labile groups that contain an optionally substituted cycloalkyl group having 3 ring carbon atoms.

31. The photoresist of claim 29 wherein the polymer comprises pendant acid-labile groups that contain an optionally substituted cycloalkyl group having 4 ring carbon atoms.